Guojin Chen

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Current Position

Research Scientist Intern, NVIDIA Research, Austin, Texas	2024.04 - Present
Ph.D. Candidate, The Chinese University of Hong Kong (Supervisor : Prof. Bei Yu)	2021.08 - Present
Education	

Ph.D. in Computer Science, *The Chinese University of Hong Kong* Supervisor: Prof. Bei Yu

M.S. in Computer Science, The Chinese University of Hong Kong 2019 – 2020 B.S. in Computer Science, Huazhong University of Science and Technology 2015 – 2019

Research Interests

- O Scaling deep learning: large language models, LLM on EDA, large-scale layout representaion learning.
- O Design for manufacturing: computational lithography, mask optimization, OPC, SMO.
- O Deep learning in VLSI design: physics-informed networks for EDA problems
- Optimization: bi-level & multi-level optimization, GPU acceleration, level-set optimization.

Experiences

Research Scientist Intern, NVIDIA, Austin, TX (Mentor & Manager. Haoyu Yang & Mark Ren) 2024.04 – Present Visiting Scholar, The University of Texas at Austin, Austin, TX (Supervisor: Prof. David Z. Pan) 2023.08 – 2024.4 Research Intern, Tencent, Shenzhen, China 2018 – 2019

Publications [Google Scholar; 174+ citations, h-index: 7+]

Representative publications that I am a primary author on are highlighted.

Conference papers.....

- [C15] Efficient Bilevel Source Mask Optimization

 Guojin Chen, Hongquan He, Peng Xu, Hao Geng, and Bei Yu

 (DAC 2024) ACM/IEEE Design Automation Conference
- [C14] Fracturing-aware Curvilinear ILT via Circular E-beam Mask Writer Xinyun Zhang, Su Zheng, Guojin Chen, Binwu Zhu, Hong Xu, and Bei Yu (DAC 2024) ACM/IEEE Design Automation Conference
- [C13] Performance-driven Analog Routing via Heterogeneous 3DGNN and Potential Relaxation Peng Xu, Guojin Chen, Keren Zhu, Tinghuan Chen, Tsung-Yi Ho, and Bei Yu (DAC 2024) ACM/IEEE Design Automation Conference
- [C12] Open-Source Differentiable Lithography Imaging Framework Guojin Chen, Hao Geng, Bei Yu, and David Z. Pan (SPIE 2024) SPIE Advanced Lithography + Patterning
- [C11] AlphaSyn: Logic Synthesis Optimization with Efficient Monte Carlo Tree Search Zehua Pei, Fangzhou Liu, Zhuolun He, Guojin Chen, Haisheng Zheng, Keren Zhu, and Bei Yu (ICCAD 2023) Proceedings of the 42th International Conference on Computer-Aided Design
- [C10] Physics-Informed Optical Kernel Regression Using Complex-valued Neural Fields

 Guojin Chen, Zehua Pei, Haoyu Yang, Yuzhe Ma, Bei Yu, and Martin Wong

 (DAC 2023) ACM/IEEE Design Automation Conference (Best score in DFM track.)
 - [C9] DiffPattern: Layout Pattern Generation via Discrete Diffusion Zixiao Wang, Yunheng Shen, Wenqian Zhao, Yang Bai, Guojin Chen, Farzan Farnia, and Bei Yu (DAC 2023) ACM/IEEE Design Automation Conference

2021 - Present

- [C8] GPU-accelerated Matrix Cover Algorithm for Multiple Patterning Layout Decomposition Guojin Chen, Haoyu Yang, and Bei Yu (SPIE 2023) DTCO and Computational Patterning II
- [C7] Efficient Point Cloud Analysis Using Hilbert Curve.
 Wanli Chen, Xinge Zhu, Guojin Chen, and Bei Yu
 (ECCV 2022) European Conference on Computer Vision
- [C6] AdaOPC: A Self-Adaptive Mask Optimization Framework For Real Design Patterns Wenqian Zhao, Xufeng Yao, Ziyang Yu, **Guojin Chen**, Yuzhe Ma, Bei Yu, and Martin Wong (**ICCAD 2022**) *Proceedings of the 41th International Conference on Computer-Aided Design*
- [C5] LayouTransformer: Generating Layout Patterns with Transformer via Sequential Pattern Modeling Liangjian Wen, Yi Zhu, Lei Ye, **Guojin Chen**, Bei Yu, Jianzhuang Liu, and Chunjing Xu (ICCAD 2022) Proceedings of the 41th International Conference on Computer-Aided Design
- [C4] DevelSet: Deep Neural Level Set for Instant Mask optimization

 Guojin Chen, Ziyang Yu, Hongduo Liu, Yuzhe Ma, and Bei Yu

 (ICCAD 2021) Proceedings of the 40th International Conference on Computer-Aided Design
- [C3] Learning Point Clouds in EDA.
 Wei Li, Guojin Chen, Haoyu Yang, Ran Chen, and Bei Yu
 (ISPD 2021) ACM International Symposium on Physical Design
- [C2] DAMO: Deep Agile Mask Optimization for Full Chip Scale **Guojin Chen**, Wanli Chen, Yuzhe Ma, Haoyu Yang, and Bei Yu

 (ICCAD 2020) Proceedings of the 39th International Conference on Computer-Aided Design
- [C1] A GPU-enabled Level Set Method for Mask Optimization Ziyang Yu, Guojin Chen, Yuzhe Ma, and Bei Yu (DATE 2020) IEEE/ACM Proceedings Design, Automation and Test in Europe

Journal papers...

- [J6] DeepOTF: Learning Equations-constrained Prediction for Electromagnetic Behavior Peng Xu, Siyuan Xu, Tinghuan Chen, Guojin Chen, Tsung-Yi Ho, and Bei Yu (TODAES 2024) ACM Trans. Des. Autom. Electron. Syst.
- [J5] Ultra-Fast Source Mask Optimization via Conditional Discrete Diffusion

 Guojin Chen, Zixiao Wang, Bei Yu, David Z. Pan, and Martin D.F. Wong

 (TCAD 2024) IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems
- [J4] L2O-ILT: Learning to Optimize Inverse Lithography Techniques
 Binwu Zhu, Su Zheng, Ziyang Yu, **Guojin Chen**, Yuzhe Ma, Fan Yang, Bei Yu, and Martin Wong
 (**TCAD 2023**) *IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems*
- [J3] A GPU-Enabled Level-Set Method for Mask Optimization
 Ziyang Yu, Guojin Chen, Yuzhe Ma, and Bei Yu
 (TCAD 2023) IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems
- [J2] DevelSet: Deep Neural Level Set for Instant Mask optimization

 Guojin Chen, Ziyang Yu, Hongduo Liu, Yuzhe Ma, and Bei Yu

 (TCAD 2023) IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems
- [J1] DAMO: Deep Agile Mask Optimization for Full-Chip Scale

 Guojin Chen, Wanli Chen, Qi Sun, Yuzhe Ma, Haoyu Yang, and Bei Yu

 (TCAD 2022) IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems

Preprints

[P1] LLM-Enhanced Bayesian Optimization for Efficient Analog Layout Constraint Generation Guojin Chen, Keren Zhu, Seunggeun Kim, Hanqing Zhu, Yao Lai, Bei Yu, and David Z Pan (arXiv 2024) arXiv preprint arXiv:2406.05250

Open Source Repositories

1. TorchOPC/TorchLitho — ★88 — Differentiable computational lithography with 2. OpenOPC/OpenILT — ★92 — Open-source inverse lithography technology (IL 3. ai4eda/awesome-AI4EDA — ★98 — A curated paper list of existing AI for EDA	T) framework 2023
Awards	
Ph.D. Studentship	2021 – 2025
By Chinese University of Hong Kong, 2021-2025 Outstanding Graduate By Huazhong University of Science and Technology	2019

Professional Activities

Paper Review / External Review	
Design Automation Conference (DAC)	2021-2023
AAAI Conference on Artificial Intelligence (AAAI)	2022-2023
IEEE Transactions on Computer-Aided Design of Integrated Circuits and Systems (TCAD)	2022-2023